

exposure light, and at least one of ultraviolet light or visible light as non-exposure light, wherein said illumination optics consists of reflective optical components.

15. (Apparatus) An apparatus according to claim 13, wherein said illumination optics and said projection optics are consisted of reflective optical components, and said apparatus is provided with stage system for moving a mask and a substrate base in a given direction; and a control device for scanning said mask and said substrate base concurrently with respect to projection optics, so as to imprint a mask pattern on said substrate base.

16. (Amended) An apparatus according to claim 12, wherein said wide bandwidth light source generates extreme ultraviolet light as said exposure light and generates at least one of ultraviolet light or visible light as said non-exposure light; and

when using said non-exposure light generated from said wide bandwidth light source, a gaseous substance is supplied to an optical path of said non-exposure light, and when using said exposure light generated from said wide bandwidth light source, an optical path of said exposure light is enclosed in an essentially evacuated state.

17. (Amended) An apparatus according to claim 12, wherein a wavelength selection device is provided for transmitting one of said exposure light and said non-exposure light, emitted from said wide bandwidth light source, towards illumination optics.

REMARKS

Claims 1-28 are pending. By this Amendment, claims 3,4 and 15-17 are amended to eliminate multiple dependencies. No new matter is added.